

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application.

Claims 1-29 (Cancelled)

30. (Previously Presented) A method comprising:

storing for at least two days a solution containing a subset of a group consisting of a metal ion, a complexing agent, an ammonium salt, and a strong base, wherein the subset includes at least two components of the group; and

nearer to a time of use in an electroless deposition process, using the solution to form a second electroless deposition solution containing the entire group.

31. (Cancelled)

32. (Previously Presented) The method of claim 31:

wherein the subset includes the ammonium salt and lacks the strong base; and

wherein said using includes introducing the strong base into the solution that was stored.

33. (Previously Presented) The method of claim 31:

wherein the subset includes the strong base and lacks the ammonium salt; and

wherein said using includes introducing the ammonium salt into the solution that was stored.

34. (Previously Presented) The method of claim 31:

wherein the metal ion includes a metal ion that is selected from the group consisting of a cobalt ion, a nickel ion, an iron ion, a tungsten ion, a molybdenum ion, a niobium ion, a tantalum ion, and combinations thereof;

wherein the complexing agent includes one or more carboxylic acids;

wherein the ammonium salt includes an ammonium salt that is selected from the group consisting of an ammonium halide, an ammonium carboxylate, an ammonium sulfate, and combinations thereof; and

wherein the strong base includes a base that is selected from the group consisting of a tetralkylammonium hydroxide, sodium hydroxide, and potassium hydroxide.

35. (Previously Presented) The method of claim 34:

wherein the subset includes the ammonium salt and lacks the strong base; and

wherein said using includes introducing the strong base into the stored solution.

36. (Previously Presented) The method of claim 34:

wherein the subset includes the strong base and lacks the ammonium salt; and

wherein said using includes introducing the ammonium salt into the stored solution.

37. (Previously Presented) The method of claim 30:

wherein the metal ion includes a cobalt ion, the complexing agent includes citric acid, the ammonium salt includes ammonium chloride, and the strong base includes tetramethylammonium hydroxide;

wherein the subset includes the ammonium salt and lacks the strong base; and

wherein said using includes introducing the strong base into the solution that was stored.

38. (Previously Presented) The method of claim 30:

wherein the metal ion includes a cobalt ion, the complexing agent includes citric acid, the ammonium salt includes ammonium chloride, and the strong base includes tetramethylammonium hydroxide;

wherein the subset includes the strong base and lacks the ammonium salt; and

wherein said using includes introducing the ammonium salt into the solution that was stored.

39. (Previously Presented) The method of claim 30, wherein the subset includes at least three components of the group.

40. (Previously Presented) The method of claim 30, wherein the second electroless deposition solution comprises from 0.05 to 0.5 mol/L of the metal ion, from 0.1 to 0.6 mol/L of the complexing agent, and from 0.5 to 1.5 mol/L of the ammonium salt.

41. (Previously Presented) The method of claim 30, further comprising:

adding a reducing agent to the second electroless deposition solution; and

using the resultant solution to perform an electroless deposition.

42. (Previously Presented) An electroless deposition solution prepared according to the method of claim 30.

43. (Previously Presented) An electroless deposition solution prepared according to the method of claim 32.
44. (Previously Presented) An electroless deposition solution prepared according to the method of claim 33.
45. (Previously Presented) A method comprising:
- storing for at least two days a solution that omits one or two components selected from a group consisting of a metal ion, a complexing agent, an ammonium salt, and a strong base; and
- after said storing, combining the one or two omitted components and a reducing agent with the solution to form an electroless deposition solution.
46. (Previously Presented) The method of claim 45:
- wherein the solution that is stored includes the ammonium salt and omits the strong base; and
- wherein said combining includes combining the strong base with the solution that was stored.
47. (Previously Presented) The method of claim 45:
- wherein the solution that is stored includes the strong base and omits the ammonium salt; and
- wherein said combining includes combining the ammonium salt with the solution that was stored.

48. (Previously Presented) A system comprising:
- a first source including an incomplete electroless deposition solution, the incomplete electroless deposition solution including a subset of a group consisting of a metal ion, a complexing agent, an ammonium salt, and a strong base and omitting one or two components of the group;
- a second source including the one or two omitted components of the group; and
- a fluid combination device coupled with the first source and the second source to receive the incomplete electroless deposition solution and the one or two omitted components and to introduce the one or two omitted components into the incomplete electroless deposition solution.
49. (Previously Presented) The system of claim 48, wherein the fluid combination device comprises a tee.
50. (Previously Presented) The system of claim 48:
- wherein the subset lacks the strong base; and
- wherein said using includes introducing the strong base into the solution that was stored.
51. (Previously Presented) The system of claim 50, wherein the subset includes the ammonium salt.
52. (Previously Presented) The system of claim 48:
- wherein the subset lacks the ammonium salt; and

wherein said using includes introducing the ammonium salt into the solution that was stored.

53. (Previously Presented) The system of claim 52, wherein the subset includes the strong base.